

## Fused silica KU1(0.17...2.2µm), KUVI(0.18...3.5µm)

| λ [nm] | KU1     |          | KUVI    |          |
|--------|---------|----------|---------|----------|
|        | n       | T(λ) [%] | n       | T(λ) [%] |
| 170.0  | 1.615   | 97.8     | 1.615   | 50.7     |
| 185.0  | 1.57502 | 99.2     | 1.57509 | 97.9     |
| 194.2  | 1.55892 | 99.3     | 1.55899 | 99.0     |
| 214.4  | 1.53372 | 99.6     | 1.53379 | 99.6     |
| 280.3  | 1.49404 | 99.9     | 1.49409 | 99.9     |
| 302.2  | 1.48719 | 99.9     | 1.48724 | 99.9     |
| 365.0  | 1.47454 | 99.9     | 1.47460 | 99.9     |
| 404.7  | 1.46962 | 99.9     | 1.46967 | 99.9     |
| 435.8  | 1.46662 | 99.9     | 1.46675 | 99.9     |
| 546.1  | 1.46008 | 99.9     | 1.46014 | 99.9     |
| 587.6  | 1.45846 | 99.9     | 1.45852 | 99.9     |
| 589.3  | 1.45840 | 99.9     | 1.45847 | 99.9     |
| 643.8  | 1.45670 | 99.9     | 1.45676 | 99.9     |
| 656.3  | 1.45637 | 99.9     | 1.45643 | 99.9     |
| 706.5  | 1.45515 | 99.9     | 1.45521 | 99.9     |
| 852.1  | 1.45247 | 99.9     | 1.45253 | 99.9     |
| 1014.0 | 1.45024 | 99.9     | 1.45030 | 99.9     |
| 1083.0 | 1.44941 | 99.9     | 1.44947 | 99.9     |
| 1128.7 | 1.44887 | 99.8     | 1.44893 | 99.8     |
| 1395.1 | 1.44584 | 99.8     | 1.44590 | 99.8     |
| 1709.1 | 1.44208 | 99.9     | 1.44214 | 99.9     |
| 1813.1 | 1.44070 | 99.9     | 1.44076 | 99.9     |
| 2058.1 | 1.43722 | 99.9     | 1.43730 | 99.9     |
| 2437.4 | 1.43095 | 95.0     | 1.43102 | 99.5     |
| 2500.0 |         | 79.2     |         | 99.2     |
| 2720.0 |         | 3.00     |         | 95.5     |
| 2800.0 |         | 5.00     |         | 93.5     |
| 2900.0 |         | 72.0     |         | 91.0     |
| 3000.0 |         | 81.0     |         | 88.0     |
| 3100.0 |         | 83.0     |         | 86.8     |
| 3243.9 | 1.41312 | 85.0     | 1.41319 | 86.0     |
| 3302.6 | 1.41154 | 86.0     | 1.41162 | 87.5     |
| 3507.0 | 1.40568 | 70.0     | 1.40575 | 70.0     |
| 3706.7 | 1.39929 | 31.1     | 1.39937 | 31.1     |
| 3750.0 |         | 18.0     |         | 18.0     |
| 3910.0 |         | 18.5     |         | 18.5     |
| 4000.0 |         | 15.0     |         | 15.0     |
| 4220.0 |         | 5.00     |         | 5.00     |
| 4300.0 |         | 0.70     |         | 0.70     |
| 4400.0 |         | 0.00     |         | 0.00     |

dispersion

| λ [nm]       | v(λ) | v(λ) |
|--------------|------|------|
| e-line 546.2 | 67.7 | 67.7 |
| d-line 587.7 | 67.8 | 67.8 |

The high quality synthetic fused silica of both types KU1 and KUVI for standard optical as well as for high power laser applications is available preformed and prepolished. KU1 is mainly used for the wavelengths in the UV-range. KUVI is the broad band fused silica with good transmission between 2µm and 3.5µm and the rest absorption below 1ppm/cm at 1000...1100nm.

density: 2.23 g/cm<sup>3</sup>  
CTE@0-200°C: 5.5x10<sup>-6</sup>/K1100nm.

recommended polishing slurries

- OXAPABS SP
- OXAPABS 69
- OXAPABS N
- OXAPABS PLUS
- OXAPABS NANO *for finishing*

recommended polishing pads

- OXAPA polishing pad hard 8
- OXAPA polishing pad intermediate 5
- OXAPA polishing pad soft 4, 19 *for finishing*

recommended polishing pitches

- OXAPAPP 15-45